EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	37	gate same (ild or (interlayer adj dielectric)) same coplanar	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 09:44
S2	13	gate same (ild or (interlayer adj dielectric)) same ("same" adj plane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 09:47
S3	19	gate same (ild or (interlayer adj dielectric)) same ("same" adj level)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 09:48
S4	31	gate same (ild or (interlayer adj dielectric)) same ("same" adj height)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 09:54
S5	1	gate same (ild or (interlayer adj dielectric)) same ("same" adj altitude)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 10:08
S6	0	gate same (ild or (interlayer adj dielectric)) same ("same" adj tallness)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 10:10
S7	0	gate same (ild or (interlayer adj dielectric)) same ("same" adj stature)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 10:10

S8	2	gate same (ild or (interlayer adj dielectric)) same ("same" adj elevation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 10:10
S9	0	gate same (ild or (interlayer adj dielectric)) same ("same" adj (pinnacle or summit or peak or top or apex or acme or zenith or loftiness))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 10:13
S10	0	gate same (ild or (interlayer adj dielectric)) same (conductor near (metal adj silicide)) same (polysilicon or (polycrystalline adj (si or silicon)))	US-PGPUB; USPAT; USOOR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 12:26
S11	268	gate same (ild or (interlayer adj dielectric)) same (conductor near\$2 (metal adj silicide)) same (polysilicon or (polycrystalline adj (si or silicon)))	US-PGPUB; USPAT; USOOR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 12:27
S12	695	gate same (ild or (interlayer adj dielectric)) same (conduct\$3 near\$2 (metal adj silicide)) same (polysilicon or (polycrystalline adj (si or silicon)))	US-PGPUB; USPAT; USOOR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 12:27
S13	0	gate same (ild or (interlayer adj dielectric)) same (conduct\$3 adj (coupled or connected) adj (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 13:43

S14	0	gate same (ild or (interlayer adj dielectric)) same ((conduct\$3 adj (layer or film)) adj (coupled or connected) adj (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 13:44
S15	0	((conduct\$3 adj (layer or film)) adj (coupled or connected) adj (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 13:44
S16	0	((conduct\$3 adj (layer or film)) near (coupled or connected) near (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 14:04
S17	116	((conduct\$3 adj (layer or film)) with (coupled or connected) with (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 14:05
S18	455	((conduct\$3 adj (layer or film)) same (coupled or connected) same (metal adj silicide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/18 14:08

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